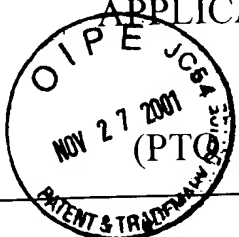


INFORMATION DISCLOSURE CITATION IN AN APPLICATION



ATTY. DOCKET NO.
50212-270

SERIAL NO.
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APPLICANT
Yoshi NISHIBAYASHI, et al.

FILING DATE
August 30, 2001

GROUP
4765-2879

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>AW</i>	6,184,611	2/6/2001	Saito et al.			


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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Yes		No	

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	Hiroshi SHIOMI et al., "High Rate Reactive Etching of Diamond and Fabrication of Porous Diamond for Field-Emission Cathode", NEW DIAMOND, Vol. 13, No. 4, pp. 28-29.
<i>AW</i>	K. Okano et al., "Mold growth of polycrystalline pyramidal-shape diamond for field emitters", DIAMOND AND RELATED MATERIALS 5, 1996, pp. 19-24. <i>no month</i>
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION				ATTY. DOCKET NO. 50212-270		SERIAL NO. 09/942,101	
				APPLICANT Yoshi NISHIBAYASHI, et al.			
 (PTO-1449)				FILING DATE August 30, 2001		GROUP 4765 2879	
				U.S. PATENT DOCUMENTS			
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						Yes	No
<i>JW</i>	10-312735	11/24/1998	Japan (English Abstract only)				RECEIVED JAN 07 2002 TC 1700
<i>JW</i>	11-204022	07/30/1999	Japan (English Abstract only)				
<i>JW</i>	WO 97/553	12/28/2000	WIPO/OMP PCT				
<i>JW</i>	WO 98/44529	10/08/1998	WIPO/OMP PCT				
<i>JW</i>	EP0836217A1	04/15/1998	EPO				
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<i>JW</i>	"Anisotropic etching of a fine column on a single crystal diamond" Nishibayashi et al., <i>Diamond and Related Materials</i> , Elsevier Science Publishers, Amsterdam, NL, Vol. 10, NR. 9-10, pp. 1732-1735, ISSN: 0925-9635						
	7th International Conference on New Diamond Science and Technology, July 23, 2000, Hong Kong, China						
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